

FIG. 1

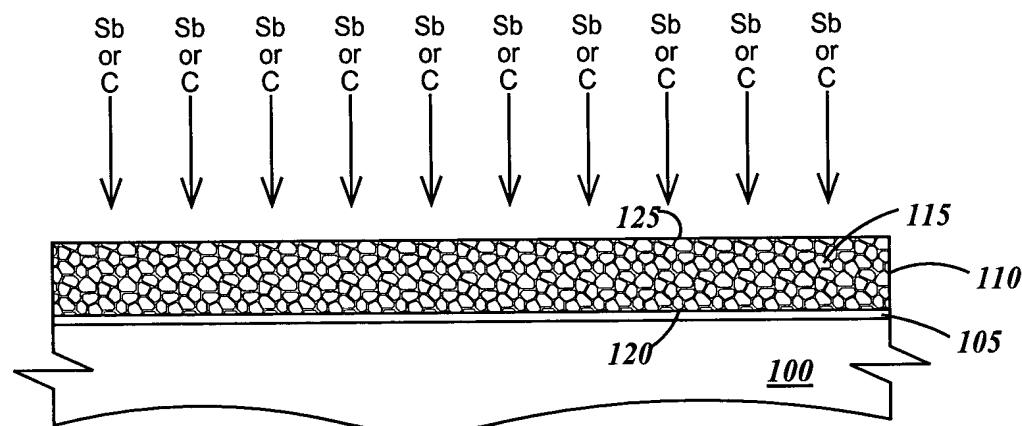


FIG. 2

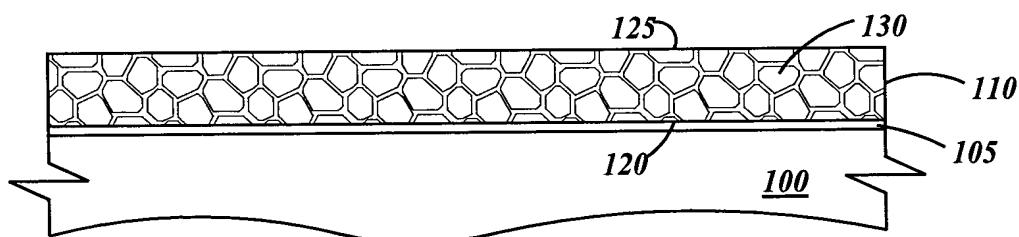


FIG. 3A

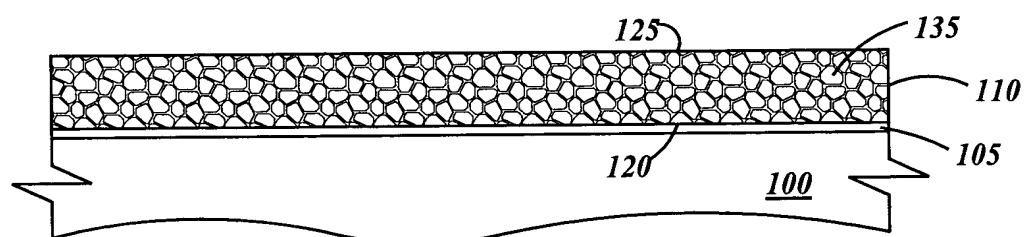


FIG. 3B

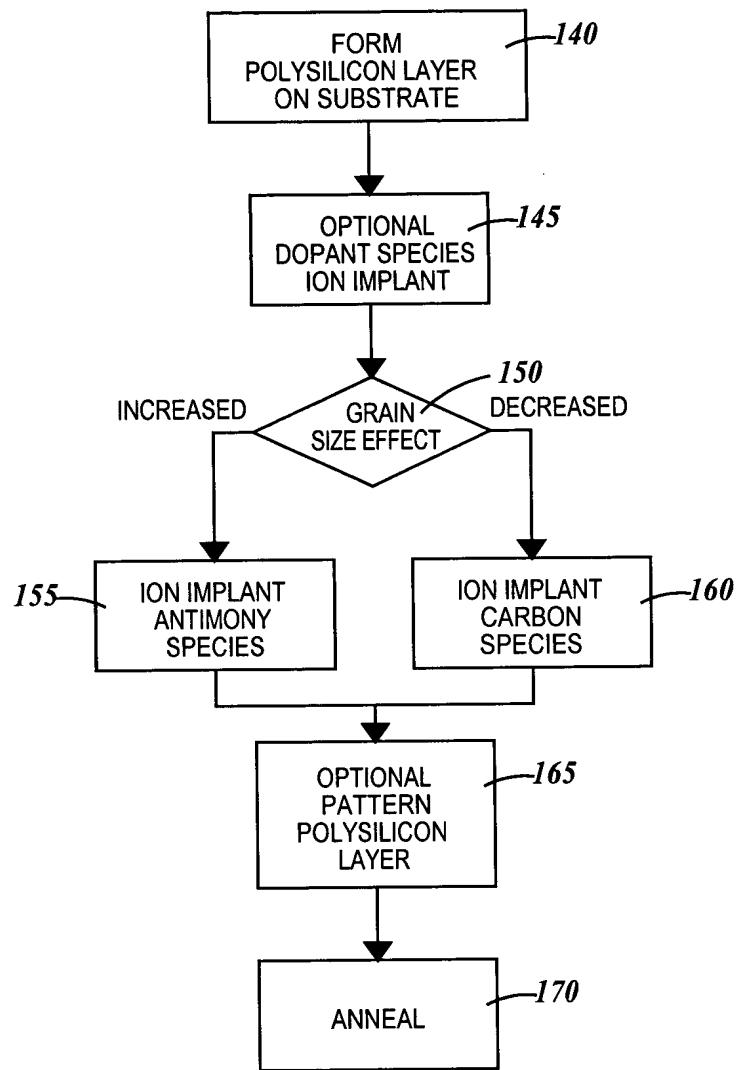


FIG. 4

EFFECT OF CARBON AND ANTIMONY IMPLANT
ON POLYSILICON GRAIN SIZE

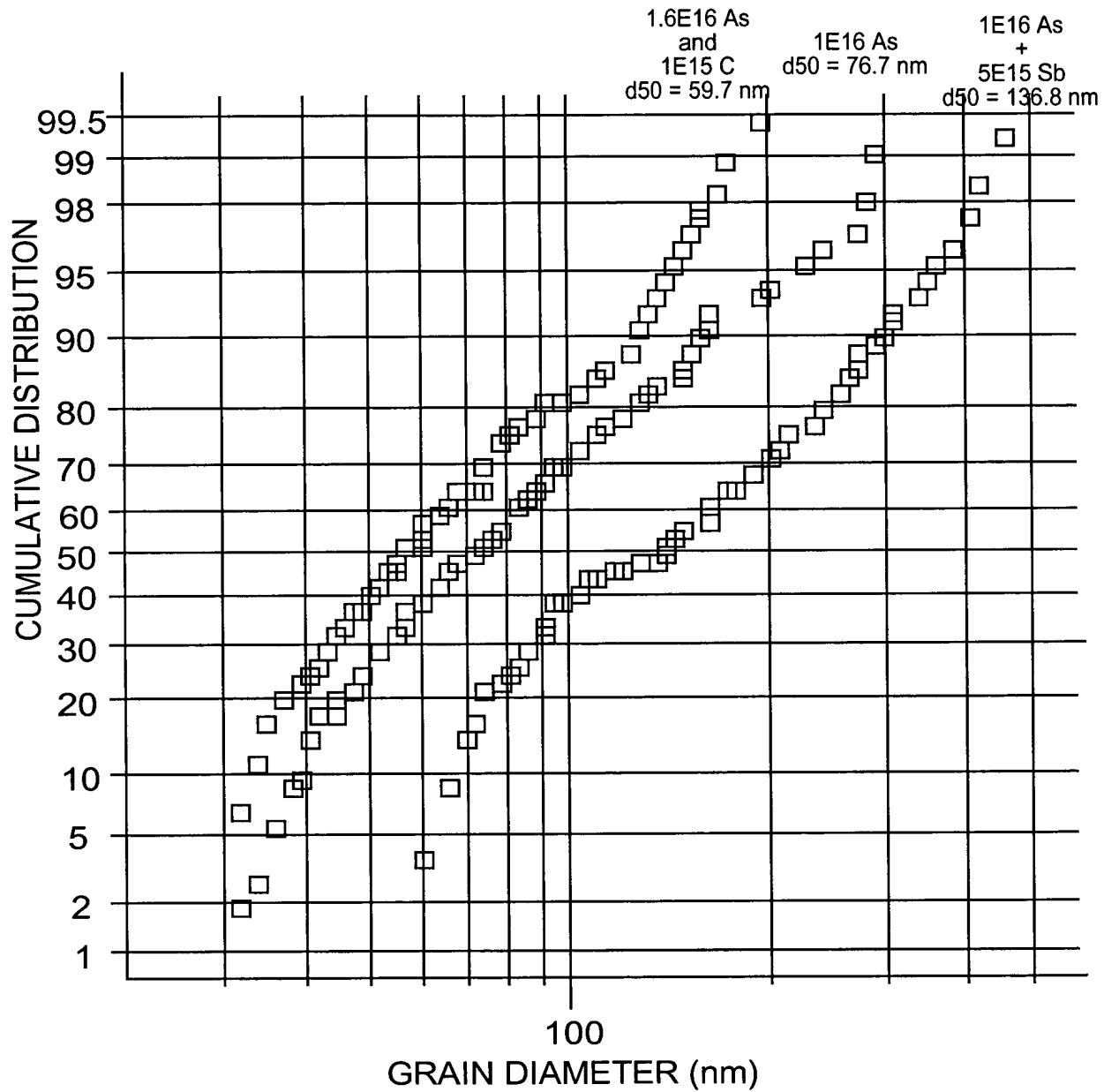


FIG. 5

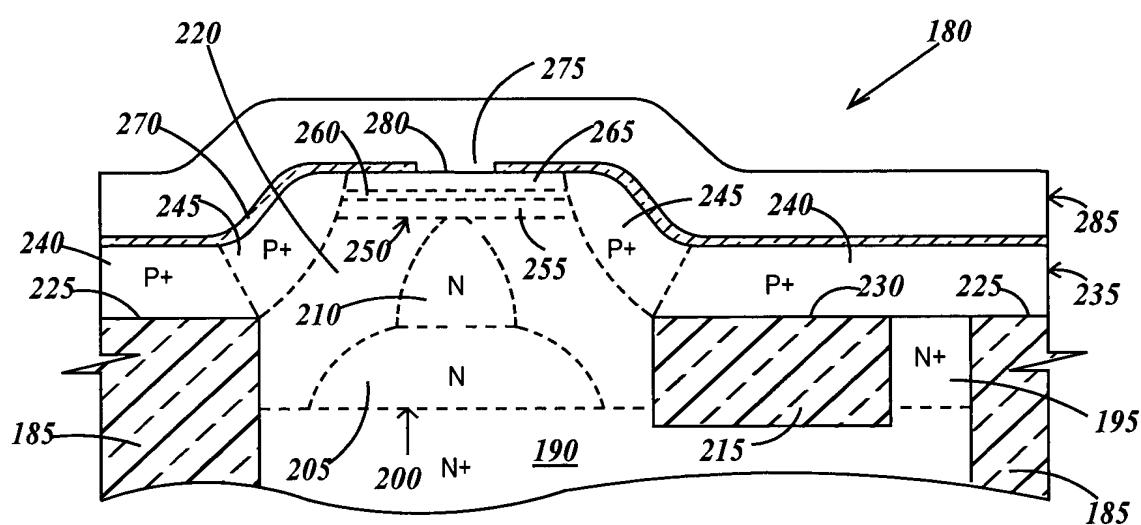
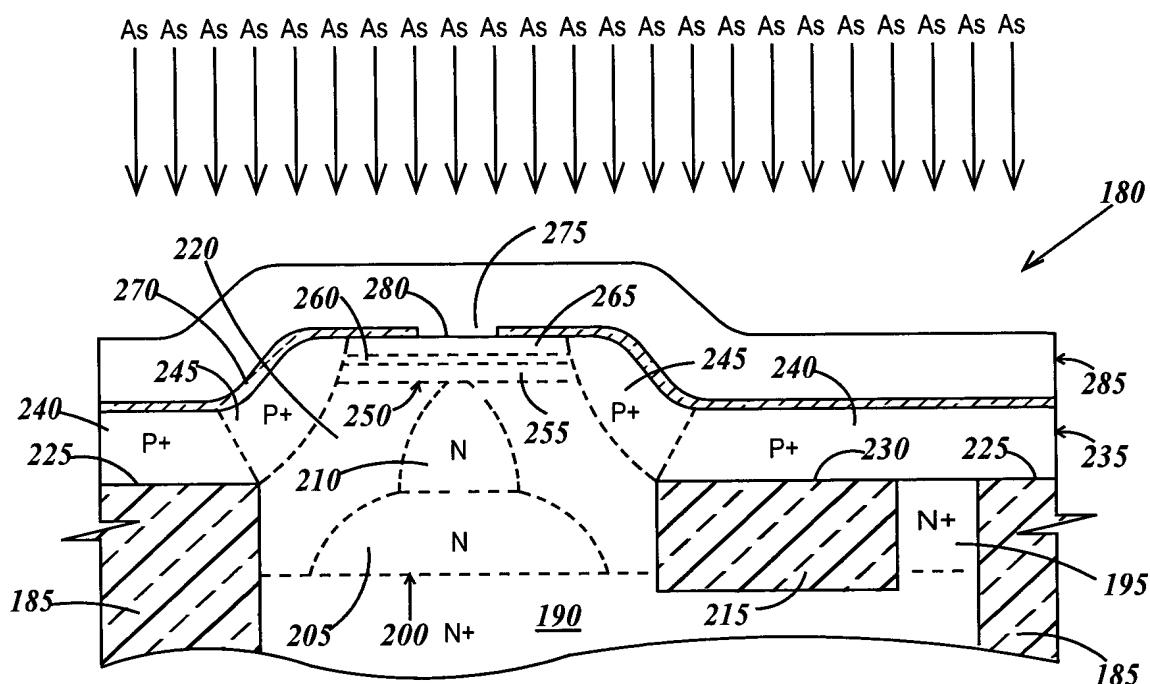


FIG. 6



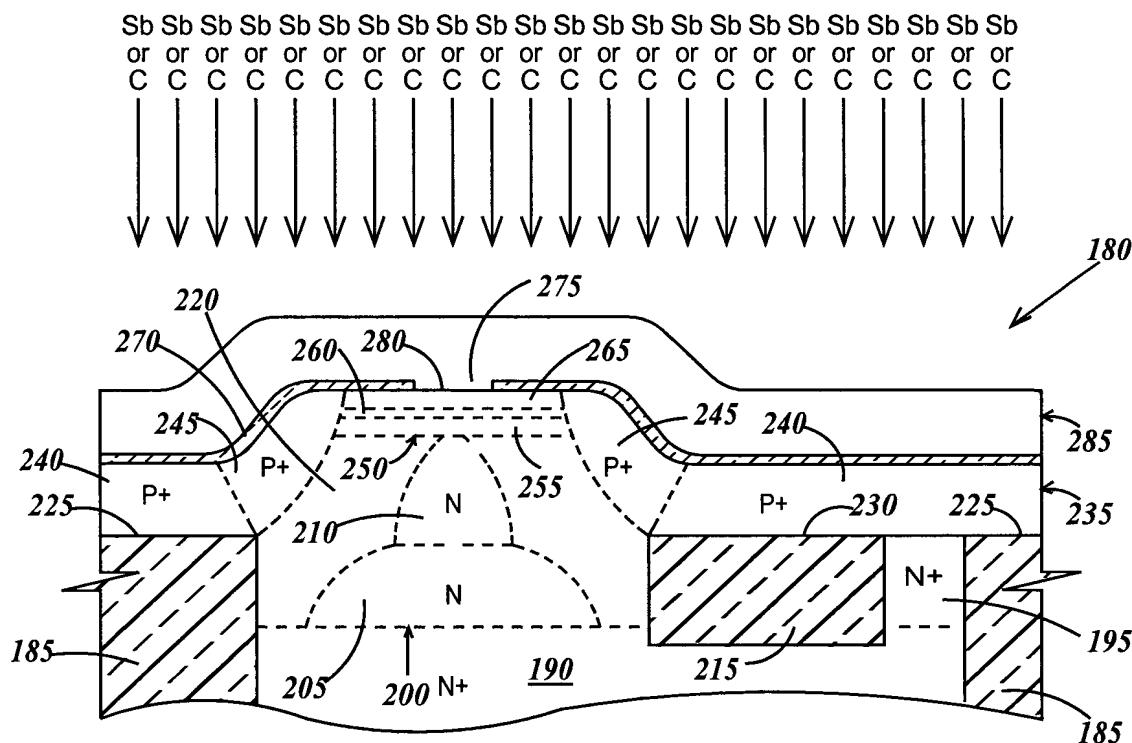


FIG. 8

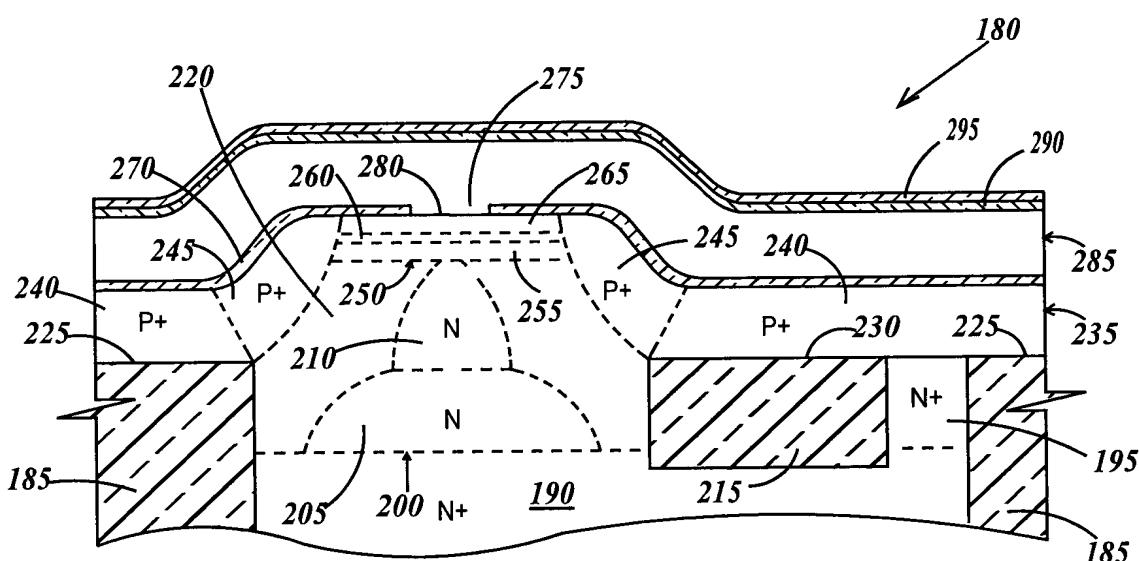


FIG. 9

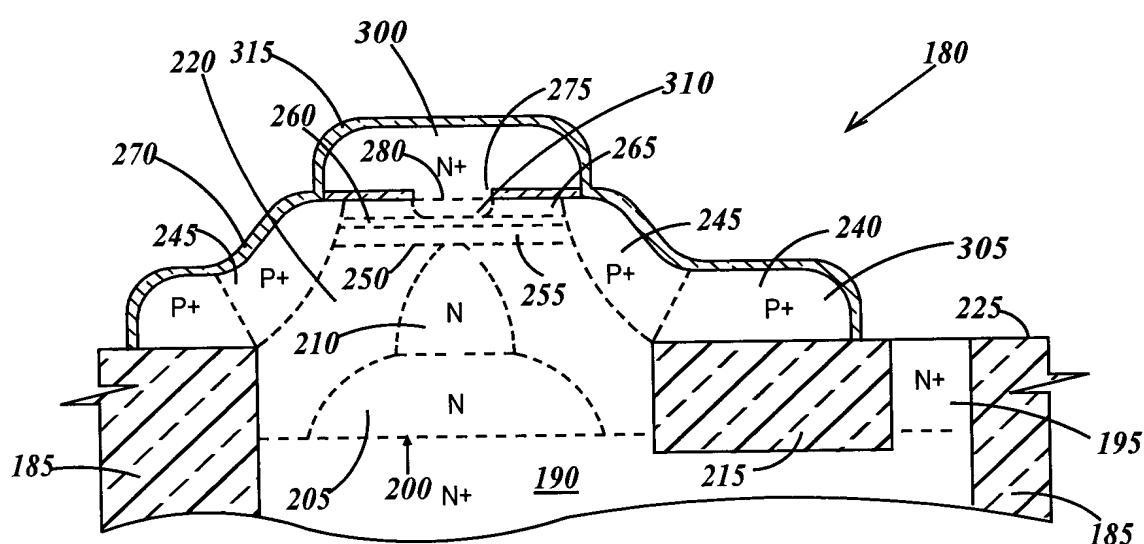


FIG. 10

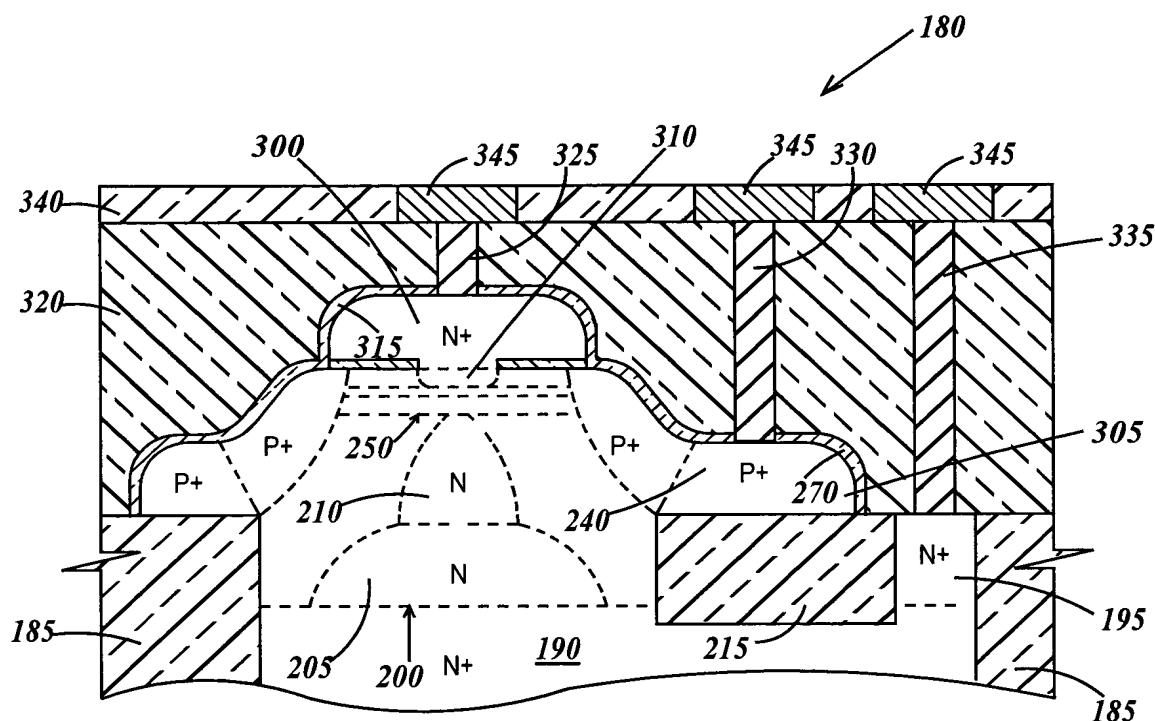


FIG. 11

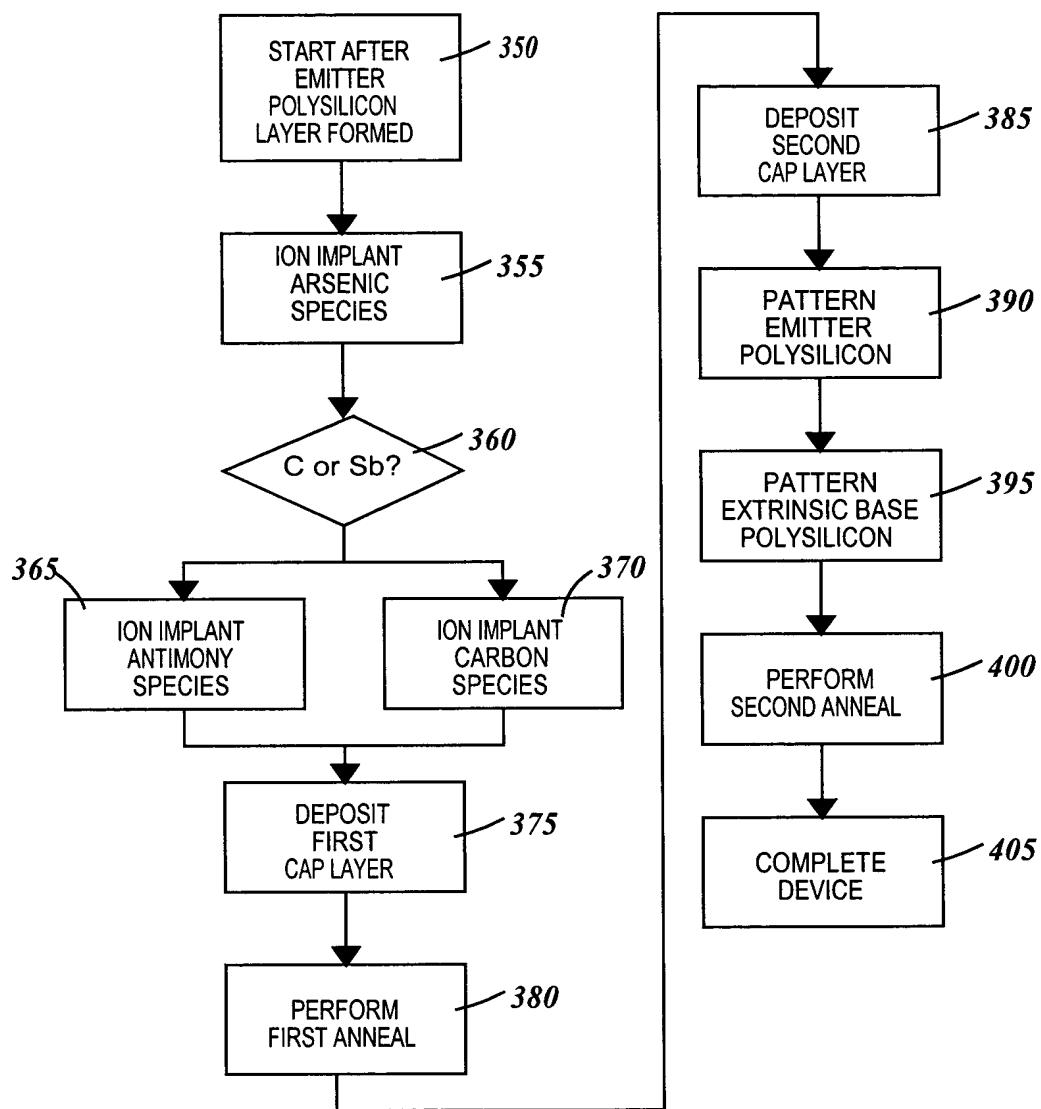


FIG. 12

**CONCENTRATION VS. DEPTH
EMITTER POLYSILICON POST RTA**

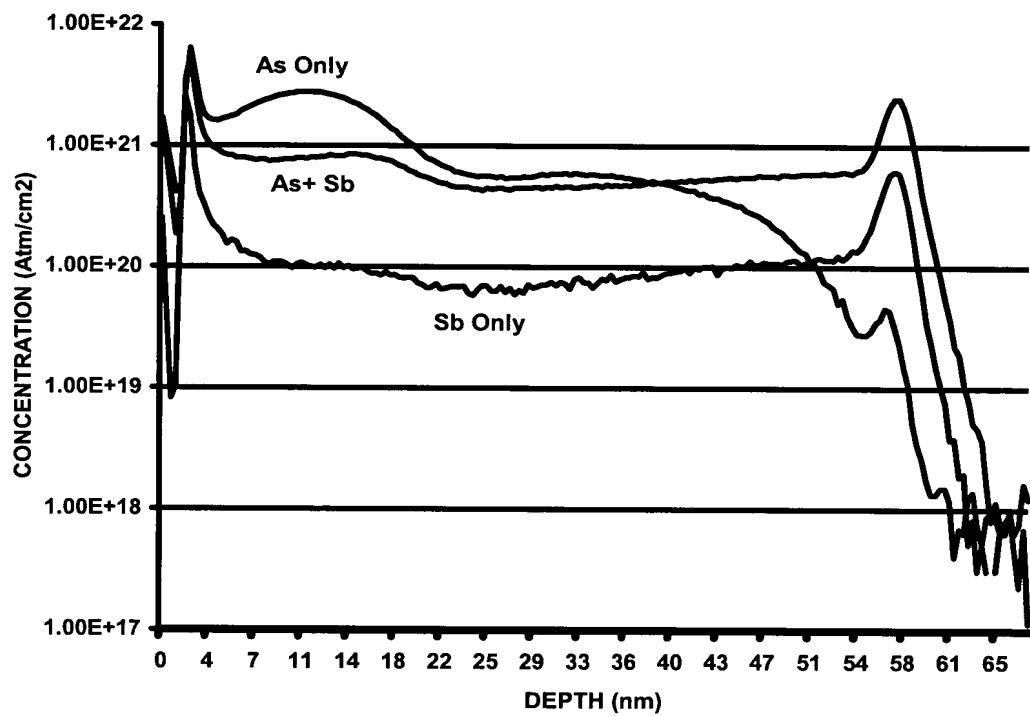


FIG. 13

NORMALIZED BASE CURRENT AS A FUNCTION
OF IMPLANT SPECIES AND DOSE

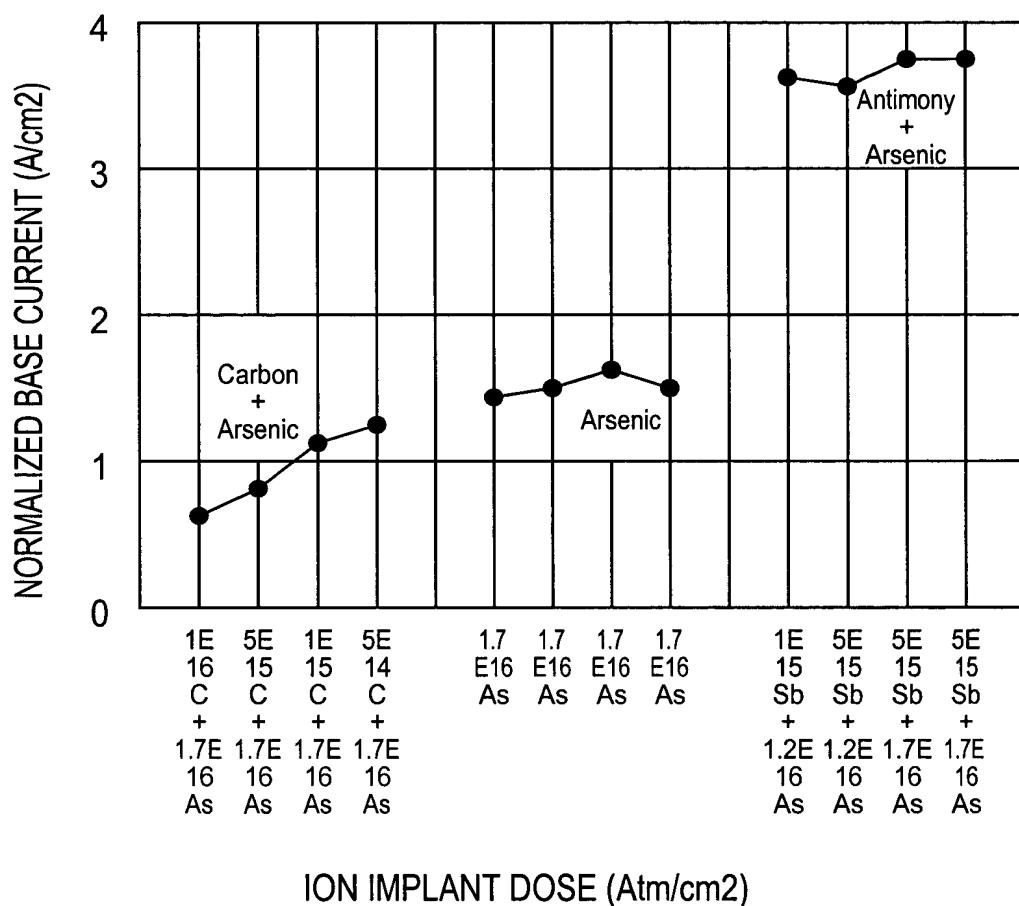


FIG. 14

EMITTER RESISTANCE AS A FUNCTION
OF IMPLANT SPECIES AND DOSE

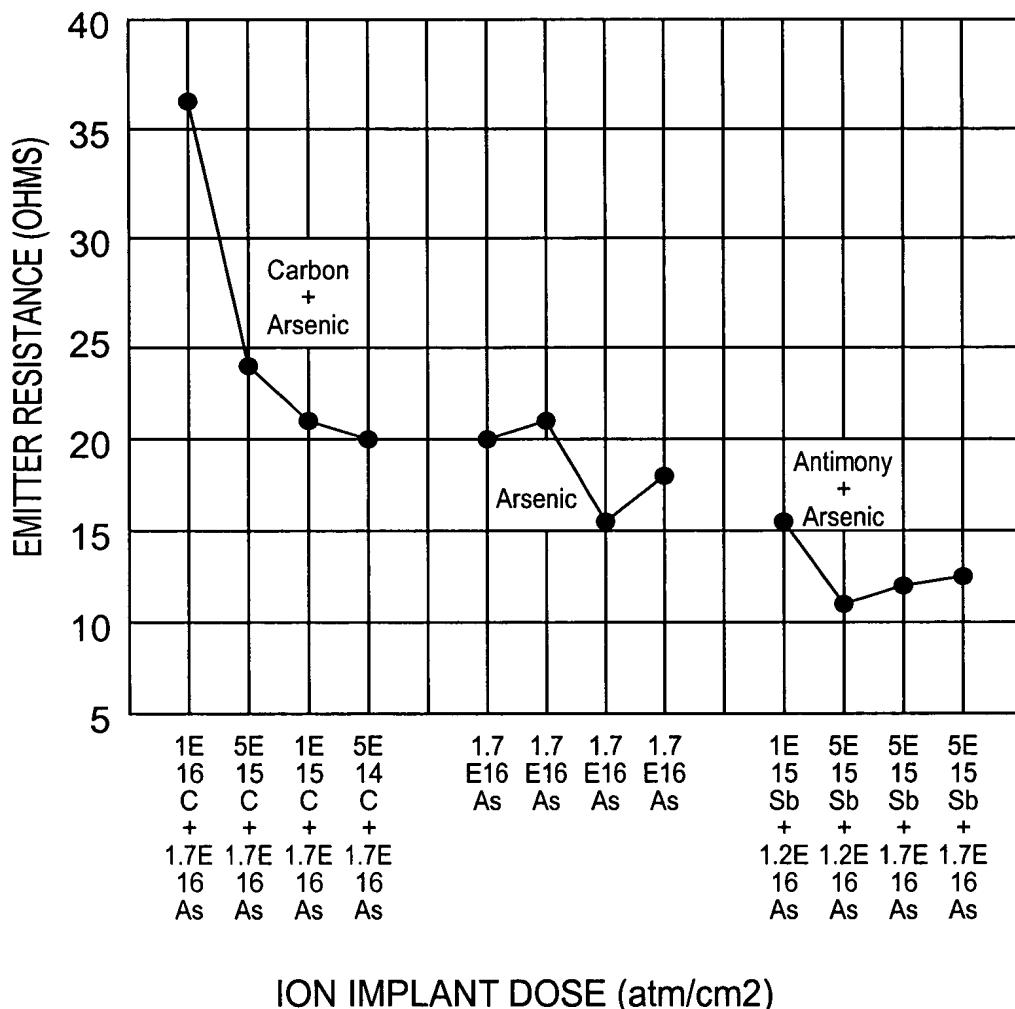


FIG. 15

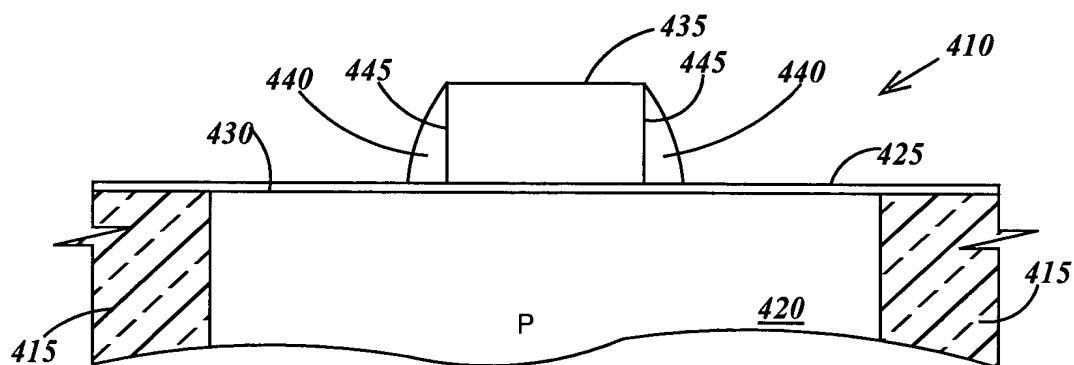


FIG. 16

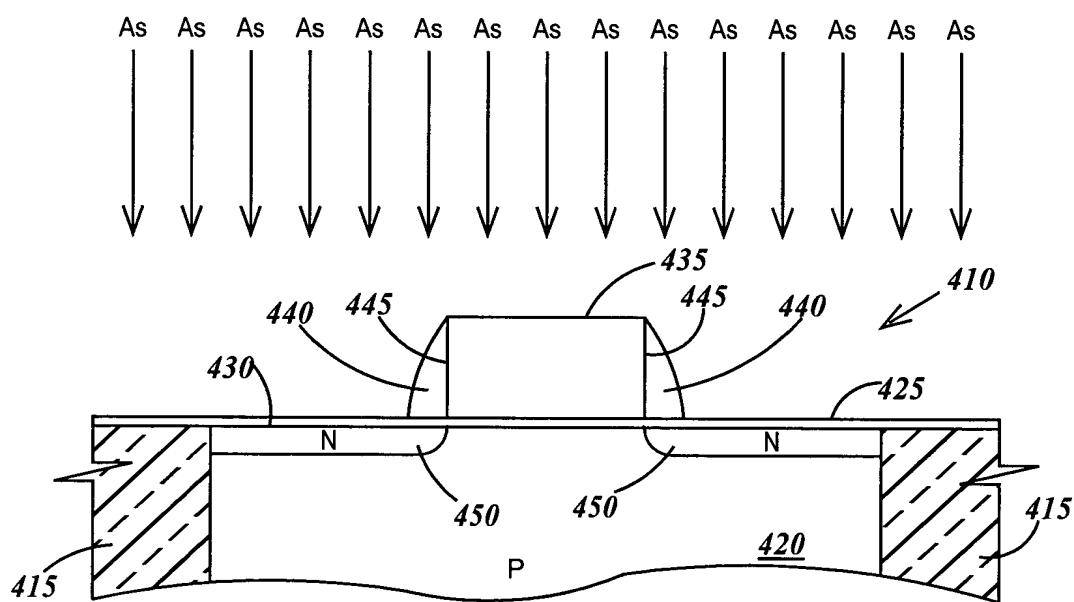


FIG. 17

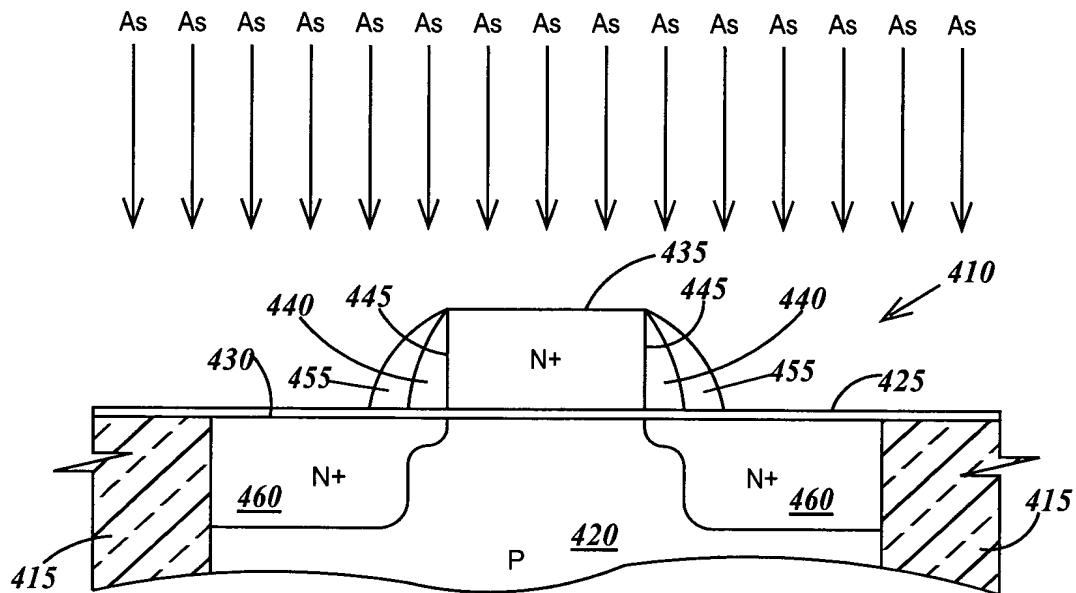


FIG. 18

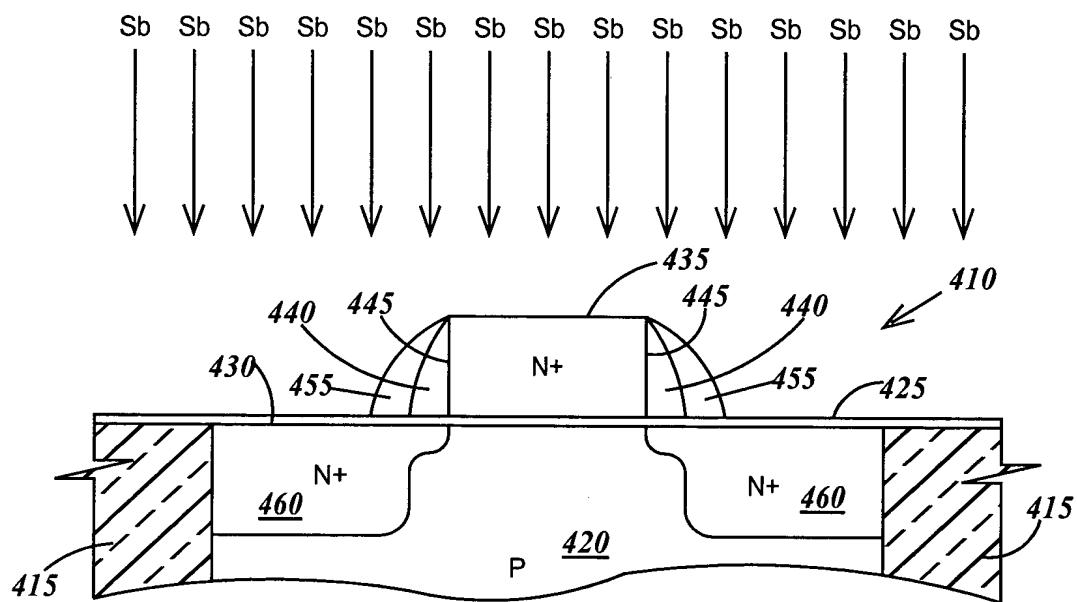


FIG. 19

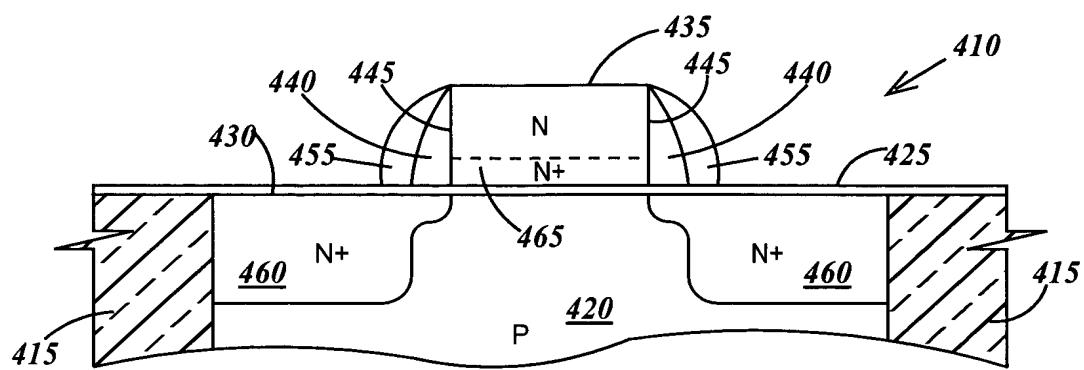


FIG. 20

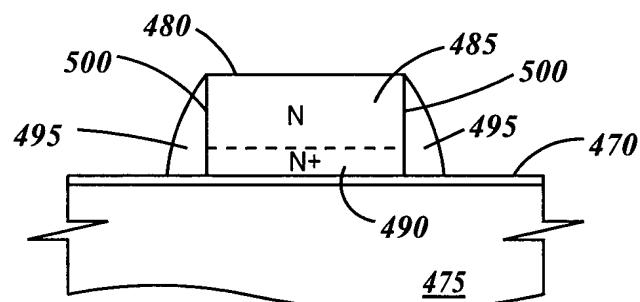


FIG. 21

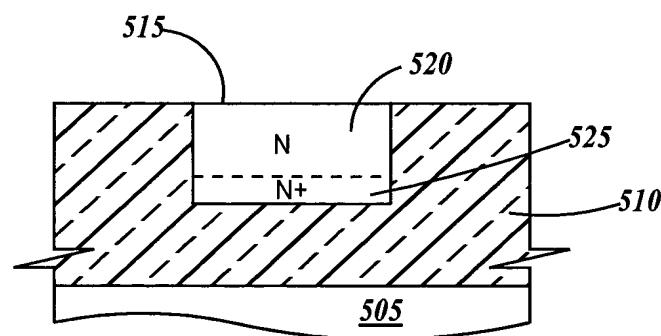


FIG. 22

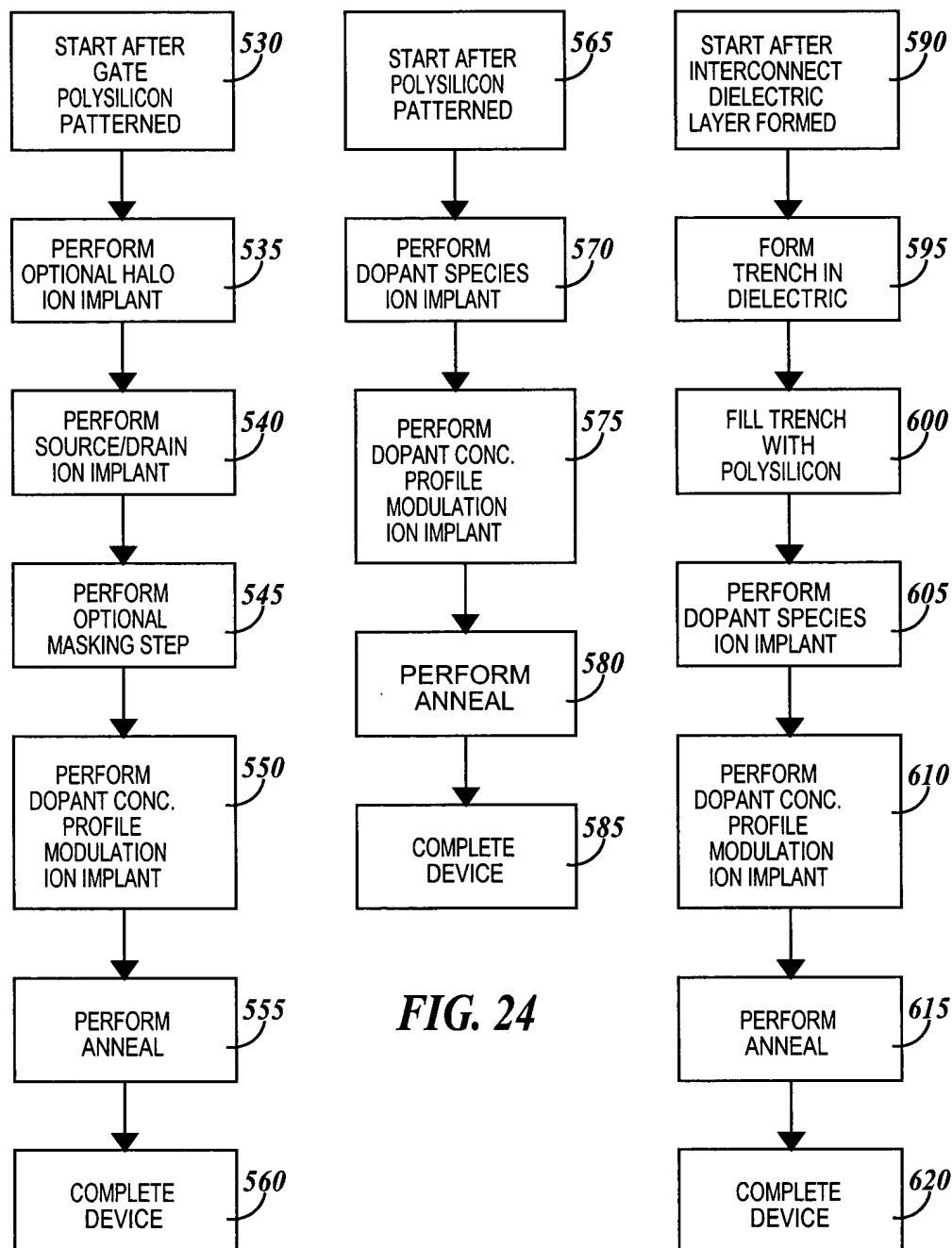


FIG. 23

FIG. 24

FIG. 25